

In the Specification

Please amend paragraph 0017 on page 5 as follows:

[0017] Fig. 6 is a colored illustration showing a top view of a fragment of a prior art radiation patterning tool (specifically, a reticle), and a graph showing a simulated contact pattern formed from the reticle with a spatial coherence of the lithography system (σ) of 0.35. The system wavelength for the simulation was 248 nanometers, and the numerical aperture was 0.70.